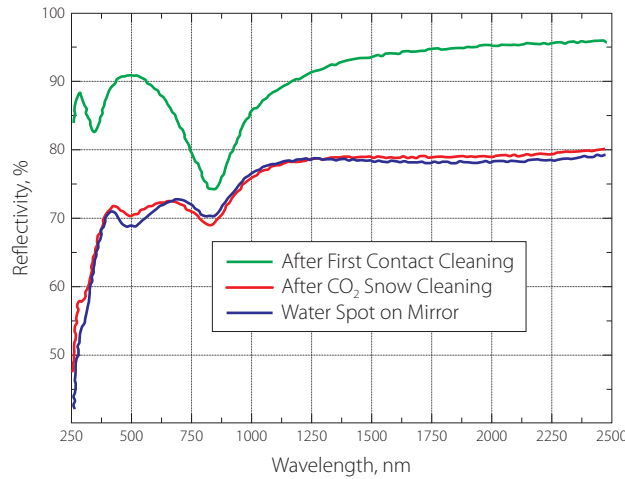


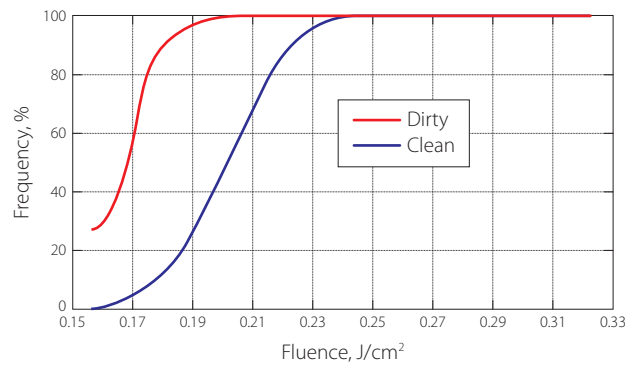
FIRST CONTACT™ GENERAL TECHNICAL INFORMATION

First Contact™ removes organic particles, dust, atmospheric particulates and other residue from optical surfaces.

Al:SiO_x mirror reflectivity data chart (courtesy of NASA) shows first surface mirror reflectivity with water spot on mirror, after CO₂ snow cleaning and after First Contact™ cleaning.



The statistical average of 355 nm laser shots that result in damage on a silicon wafer on a LDT system consisting of two nanosecond YAG lasers (600 mJ doubled and tripled Continuum Surelite and 50 mJ Minilite II with doubling, tripling and quadrupling optics). The onset of damage is delayed for the cleaned sample.



First Contact™ leaves no residue. After peeling the polymer of a thin film coated optic, XPS spectroscopy test reveals only components of the polymer, there are no traces of thin film. Expected thin film lines: U-380 eV, V-515 eV, Sc-400 eV.

